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quickly, and the throughput is improved.

(57) Abstract:

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PURPOSE: To quickly execute a defect inspection of a mask pattern, and to improve the throughput by forming a collating pattern being a comparing pattern of all or a part of mask patterns, on the outside of an area to be transferred of the mask pattern.

CONSTITUTION: Collecting patterns 3a, 3b being comparing patterns of a mask pattern 2 are formed on the outside of an area to be transferred 1a of a glass substrate 1. At the time of detecting a defect of the mask pattern 2, a light beam is projected from a mercury lamp 5, radiated simultaneously to the mask pattern 2 and its collating patterns 3a, 3b, and the light which has transmitted through the glass substrate 1 is condensed onto image sensors 8a, 8b by condensing lenses 7c, 7d placed in the upper part of a reticle L. Analog output signals from the image sensors 8a, 8b are sent to a defect detecting circuit 10 through video amplifiers 9a, 9b, compared by the defect detecting circuit 10, and a defect is detected. In such a way, a defect inspection of the mask pattern is executed

